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PATENT ABSTRACTS OF JAPAN

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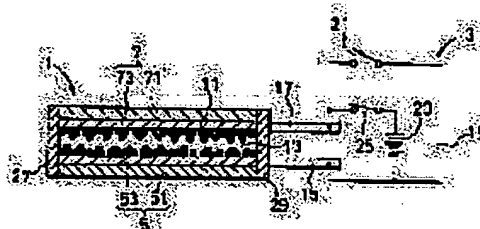
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(54) RE-DISPERSION OF ELECTRIC FIELD ARRANGEABLE PARTICLE

(57)Abstract:

PROBLEM TO BE SOLVED: To make it possible to rapidly re-disperse EA particles and to exactly attain a light shielding state by impressing a first voltage to generate an electric field arrangement effect between transparent electrode plates to increase the quantity of transmitted light and impressing a second voltage to generate an electrophoresis effect between these transparent electrode plates to decrease the quantity of transmission.

SOLUTION: When the first voltage is impressed between the electrodes 5 and 7, the EA particles 11 are perpendicularly arranged between the transparent electrode layers 53 and 73 by the EA effect and chain bodies are formed. Namely, a light controller section 1 attains the light transmission state as the attenuation to the incident light quantity decreases. On the other hand, the EA particles 11 executes electrophoresis and eventually stick to the one-side surfaces of the transparent electrode layers 53, 73 when the second voltage is impressed between the transparent electrodes 5 and 7. Namely, the light controller section 1 attains the light shielding state as the attenuation to the incident light quantity increases in the state that the second voltage is impressed thereon. The light shielding state is exactly and rapidly attained by impressing the second voltage different from the first voltage between the electrodes.



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